
Two-bit-per-cell resistive switching memory device with ITO/Zn₂TiO₄/Pt structure

Shi-Xiang Chen ¹, Shouu-Jinn Chang ¹, SHENG-PO CHANG ¹, Cheng-Han Lin ¹, and Kuan-Jen Chen ¹

¹*National Cheng Kung University, Taiwan*

ZnO-TiO₂ alloy systems, such as ZnTiO₃, Zn₂TiO₄, and Zn₂Ti₃O₈, exhibited great potential as phosphors, catalysts, microwave devices, low-temperature co-fired ceramics (LTCCs), and dielectrics. Moreover, zinc titanate (Zn₂TiO₄), with an inverse spinel structure, has been used as a catalyst and dielectric in manufacturing. Its physical features, optical properties, and electrical characteristics have been studied for dielectric applications. Herein, a Zn₂TiO₄ RRAM device with an ITO/Zn₂TiO₄/Pt metal-insulator-metal (MIM) structure was fabricated and investigated. The RS behaviour of this RRAM device was systematically studied based on the forming and operation voltages, operation currents, high/low resistance ratio using methods such as RS cycle and retention time tests. The electrical properties and fabrication methods of the device were also discussed comprehensively. We discussed the fabrication procedure and device characteristics of ITO/Zn₂TiO₄/Pt resistive random-access memory (RRAM) at room temperature. Four different resistive states were obtained by applying different current compliances, all of which showed good retention characteristics with no obvious degradation and were individually distinguished after 10000 s at a read voltage of 100 mV. The set and reset voltages of the ITO/Zn₂TiO₄/Pt RRAM device were maintained within ±1 V. The device performed well at low operation voltages. The mechanisms of multilevel resistive switching characteristics were investigated to illustrate the multilevel carrier conduction phenomenon associated with Zn₂TiO₄-based RRAM devices. In this study, our group illustrated the application of zinc titanate (Zn₂TiO₄) in non-volatile memories for the first time.

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